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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

IN RE APPLICATION OF: Hiroshi MASHIMA, et al.

SERIAL NUMBER: 10/518,371

GROUP: 1715

FILED: December 28, 2004

EXAMINER: Kelly M. Gambetta

FOR: METHOD FOR PLASMA-ENHANCED CHEMICAL VAPOR DEPOSITION AND  
APPARATUS FOR PLASMA-ENHANCED CHEMICAL VAPOR DEPOSITION

**REQUEST TO CORRECT TITLE OF INVENTION**

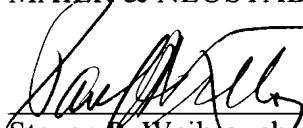
MAIL STOP ISSUE FEE  
COMMISSIONER FOR PATENTS  
P.O. BOX 1450  
ALEXANDRIA, VA 22313-1450

SIR:

In the matter of the above-identified application for patent, we hereby request  
correction of your records to reflect the correct title of the invention. The title of the  
invention should read as follows: **METHOD FOR PLASMA-ENHANCED CHEMICAL  
VAPOR DEPOSITION AND APPARATUS FOR PLASMA-ENHANCED CHEMICAL  
VAPOR DEPOSITION.**

Respectfully Submitted,

OBLON, SPIVAK, McCLELLAND,  
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